MATERIAL DATABASE

ALD MATERIALS TESTED WITH DALP®

#	MATERIAL	PREC. A	PREC. B	GROWTH RATE (Å/PASS)	CHARACTERIZATION	USE
1	Pt [a]	$(MeCp)PtMe_3$	O_3	0.55 – 1	IE, SEM, EDX, TEM, XRD, XPS, LEIS, R(T)	Mirrors
2	Al_2O_3	DMAI	H_2O	0.3	IE, SEM, EDX, TEM, XPS	Dielectric, Barrier, Protection
3	TiO_2 [a]	$Ti(O^iPr)_4$	H_2O	0.1 – 0.6	IE, SEM, EDX, TEM, XPS, transistor	Optical, Dielectric, Barrier, Protection
4	ZnO [b]	$Zn(dmap)_2$	H_2O	0.7 – 1.5	IE, SEM, EDX, AFM, XRD, XPS, transistor	Optoelectronics
5	CuO	$Cu(hfac)_2$	H_2O	0.06	IE, SEM, EDX, XRD	Photovoltaic
6	Ir	(EtCp)Ir(CHD)	O_3		IE, SEM, EDX, XRD	Conductor
7	IrO_2	(EtCp)Ir(CHD)	O_3		IE, SEM, EDX, XRD	Electrochromic devices
8	HfO_2	$Hf(NMe_2)_4$	H_2O	1.1 – 1.6	IE	Dielectric
9	SnO_2	TDMASn	H2O	0.8	SEM, EDX, I-V curve	Gas sensors, Transparent electrodes, solar cells
10	V_2O_5	TEMAV	H2O		Validated	thermochromic windows; Electrochromic device
11	WO_3	Wawona™	O_3		Upcoming	anti-bacterial & self-cleaning surfaces
12	MgF_2	Magna™	O_3	0.4 – 0.6	Validated	Anti-reflective coatings, UV optics
13	Ga_2O_3	Galai™	O_3		Upcoming	Power Electronics
14	Nb_2O_3	Nautilus2™	O_3		Upcoming	Batteries

Would you like to know if your materials are compatible with our technology? Request a demo